

ABSTRACT

An object of the present invention is to provide a polishing pad that is excellent in durability and excellent in stability of a polishing rate. The present invention relates to a polishing pad comprising a polishing layer arranged on a base material layer, wherein the polishing layer comprises a thermosetting polyurethane foam containing roughly spherical interconnected cells having an aperture, the polyurethane foam comprises an isocyanate component and an active hydrogen-containing compound as starting components, the isocyanate component contains 90% by weight or more of diphenylmethane diisocyanate and/or a modified product thereof, the active hydrogen-containing compound contains 60 to 98% by weight of polycaprolactonepolyol, and 15 to 40% by weight of a compound having the number of functional groups reactive with an isocyanate group of 3, an isocyanate group concentration relative to a total amount of the isocyanate component and the active hydrogen-containing compound is 10 to 15% by weight, and the polishing layer has the absolute value of a change rate between compressibility A in the dry condition and compressibility B in the wet condition ($\{(B-A)/A\} \times 100$) of 100 or less.